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## ABSTRACT

Process for the Decontamination of Microlithographic Projection Exposure Devices  
(Fig. 1)

UV light and a fluid are used in a process for the decontamination of microlithographic projection exposure devices with optical elements or portions thereof, in particular of the surfaces of optical elements. A second UV light source is directed for decontamination, in intervals between exposures, toward at least a portion of the optical elements.